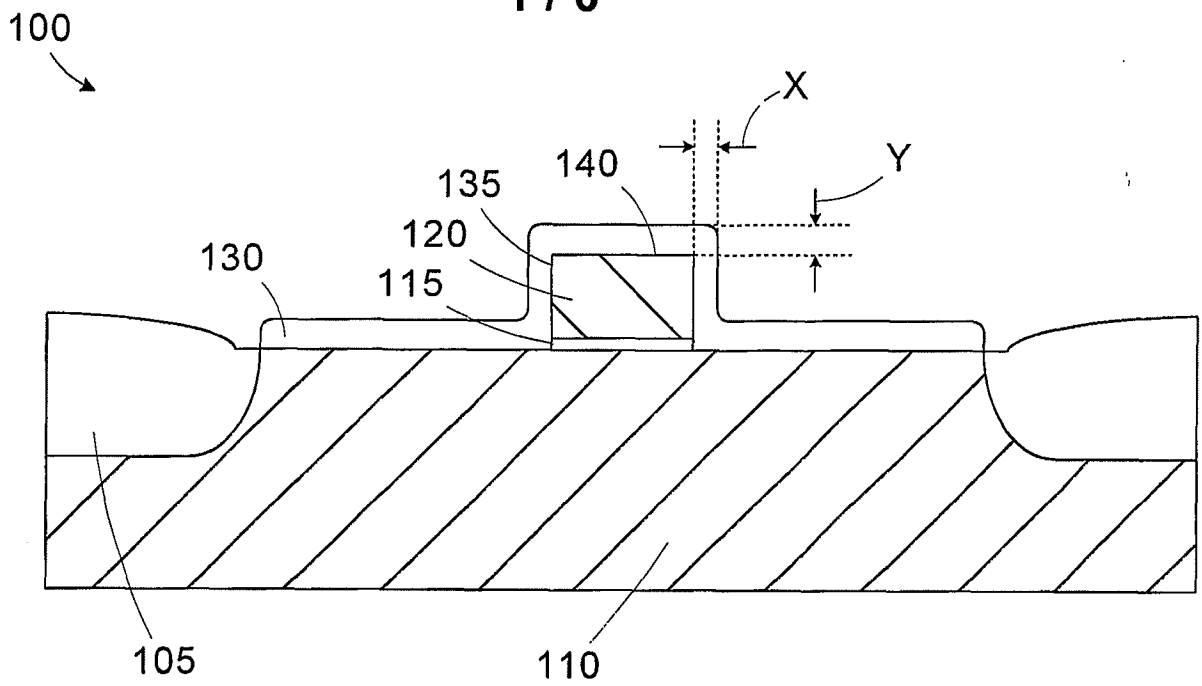



Figure 1A
(Prior Art)

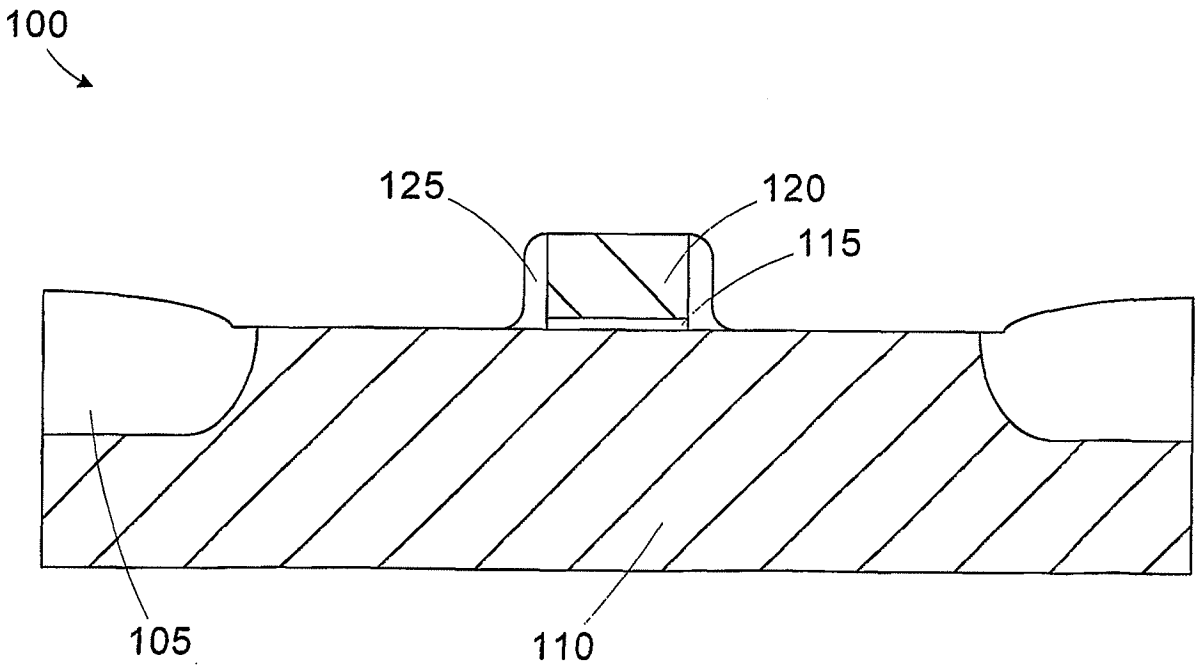



Figure 1B
(Prior Art)

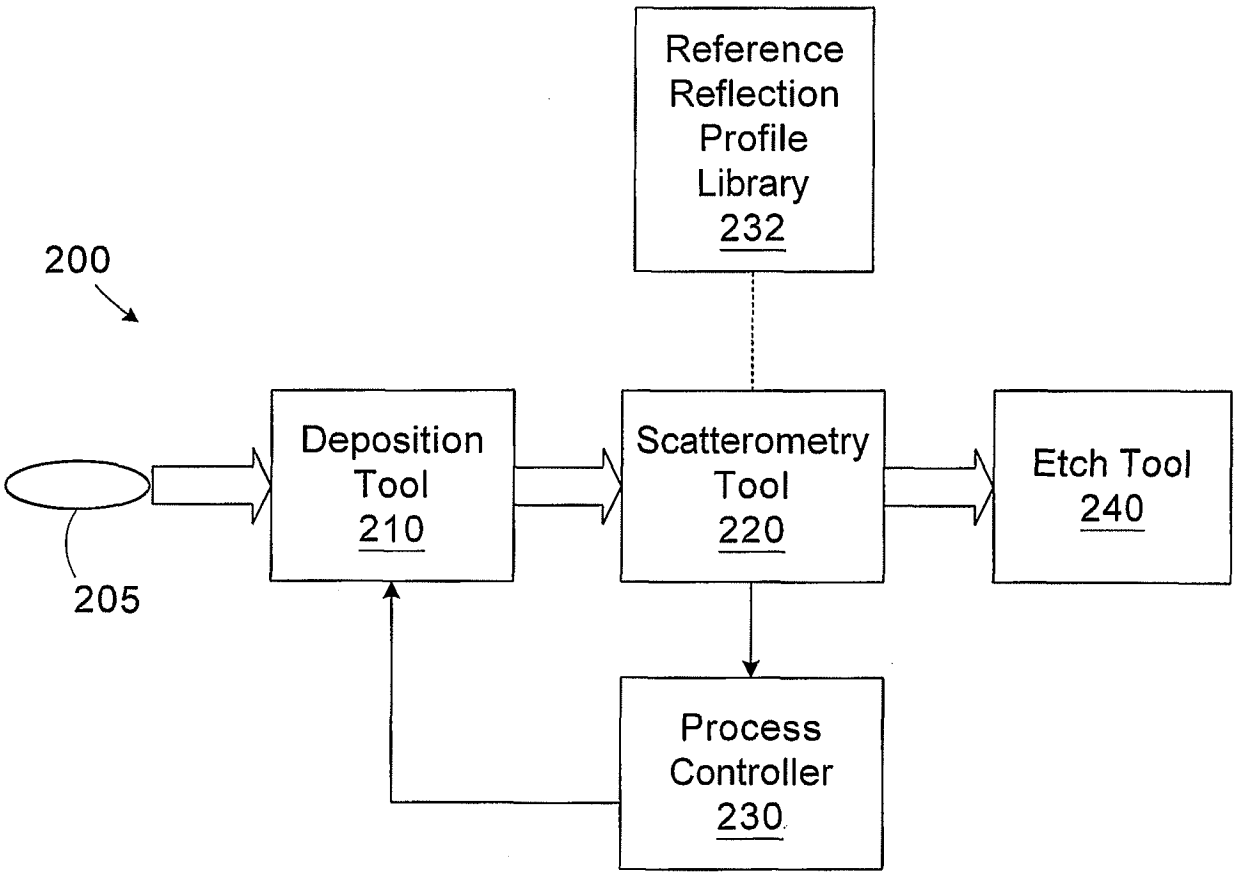

Reference Reflection Profile Library 232
200
Deposition Tool 210
Scatterometry Tool 220
Etch Tool 240
205
Process Controller 230

Figure 2

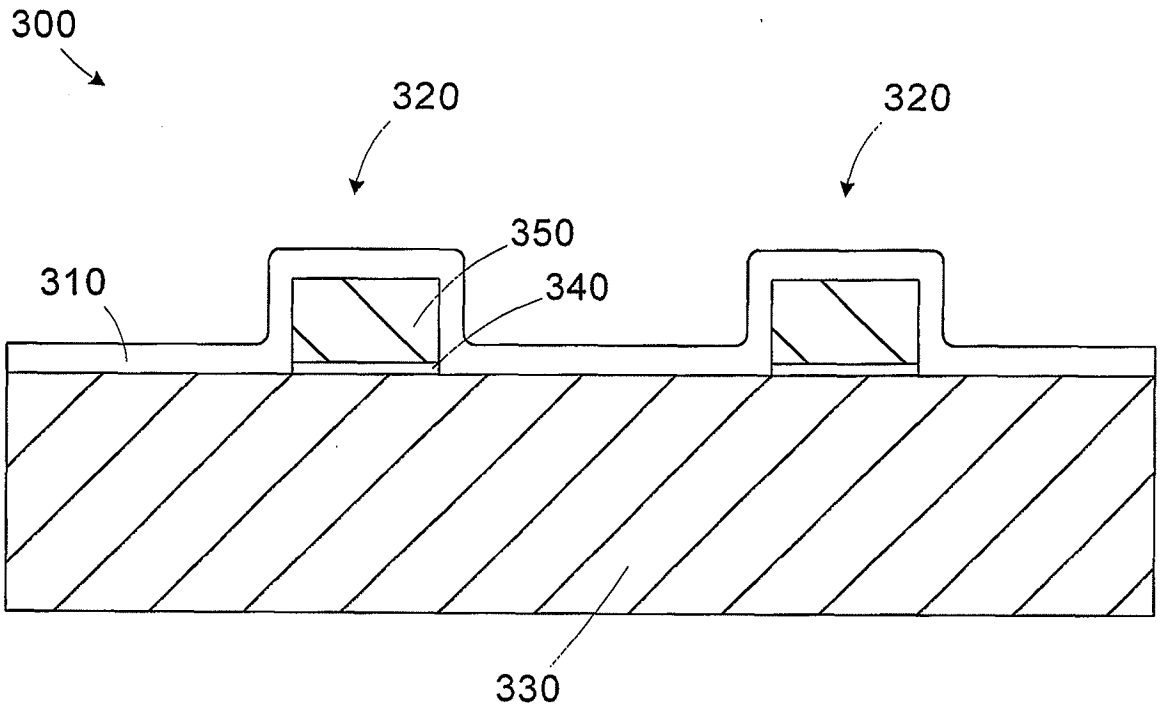



Figure 3

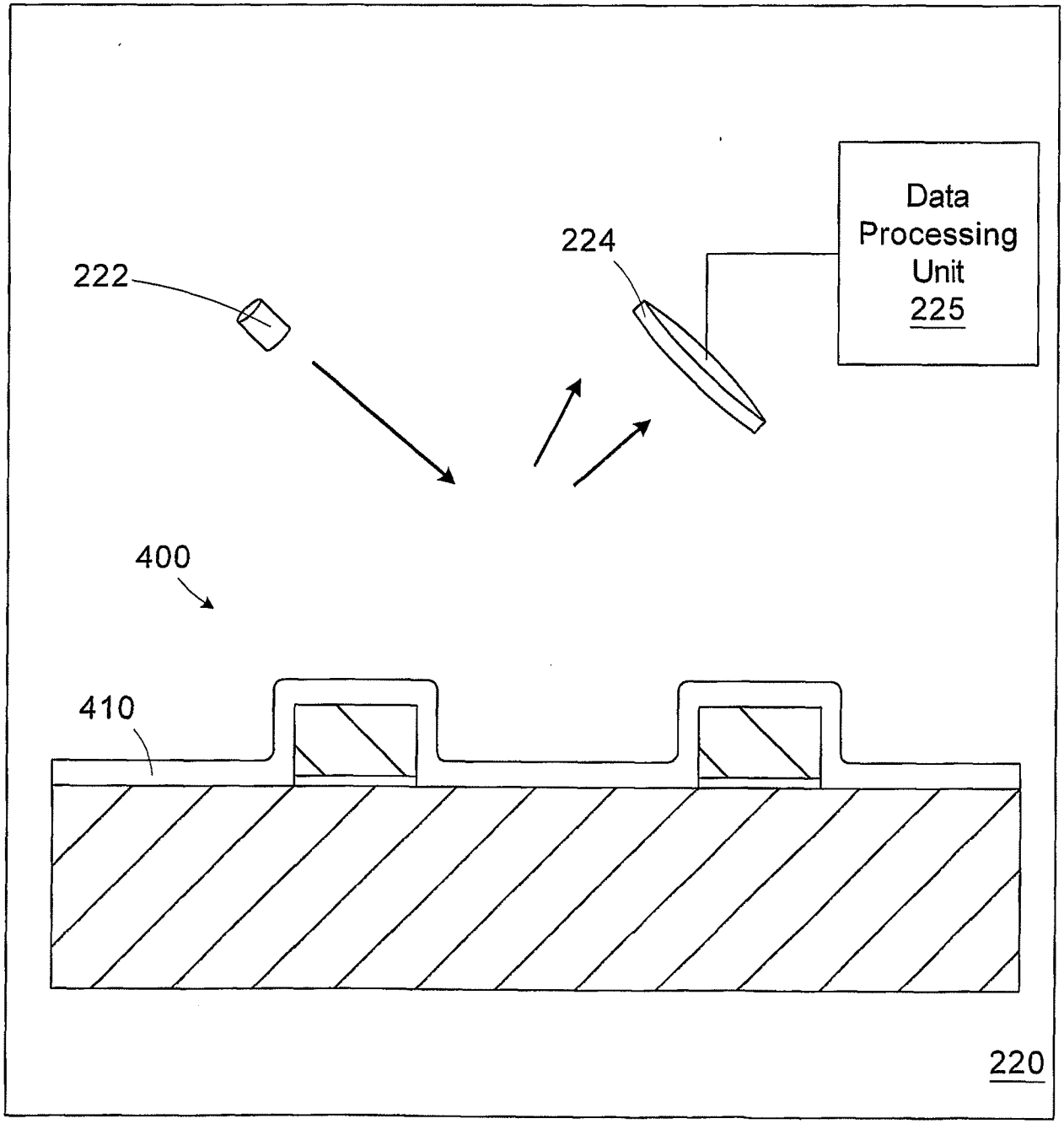



Figure 4

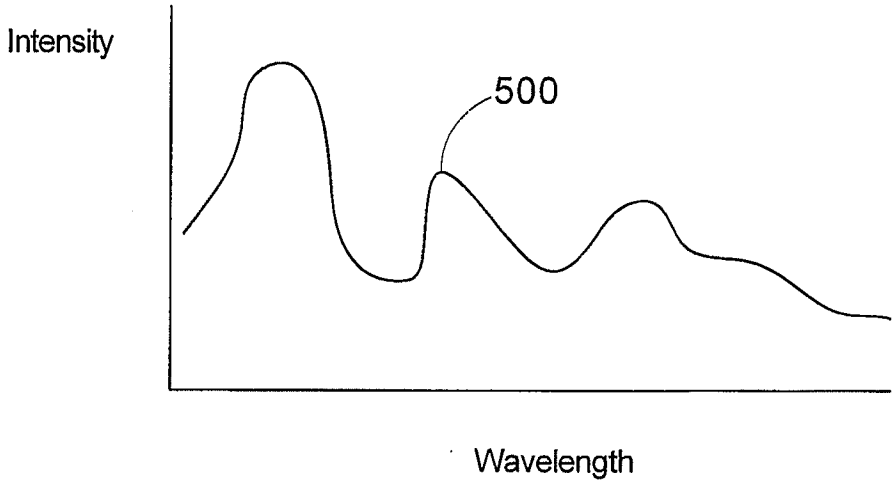



Figure 5A

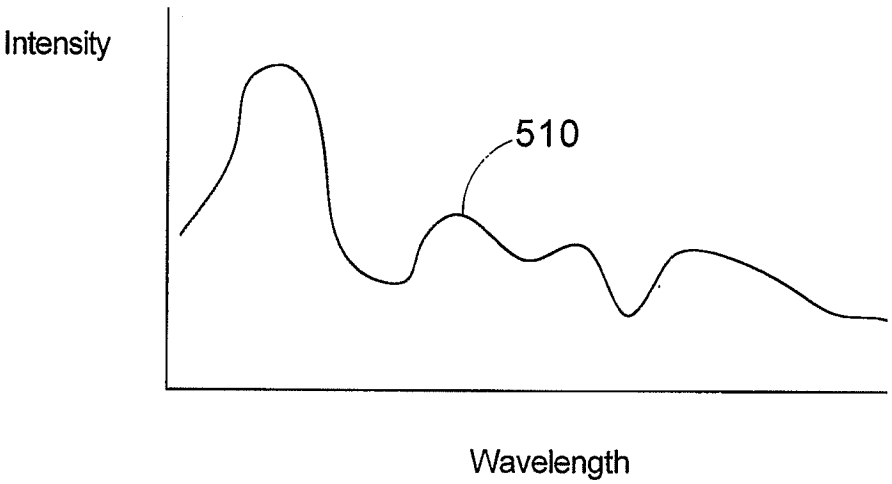



Figure 5B

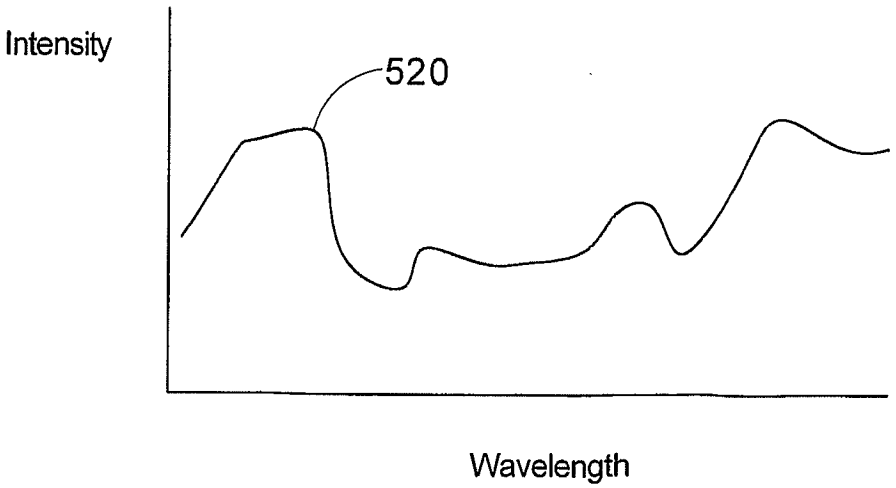



Figure 5C

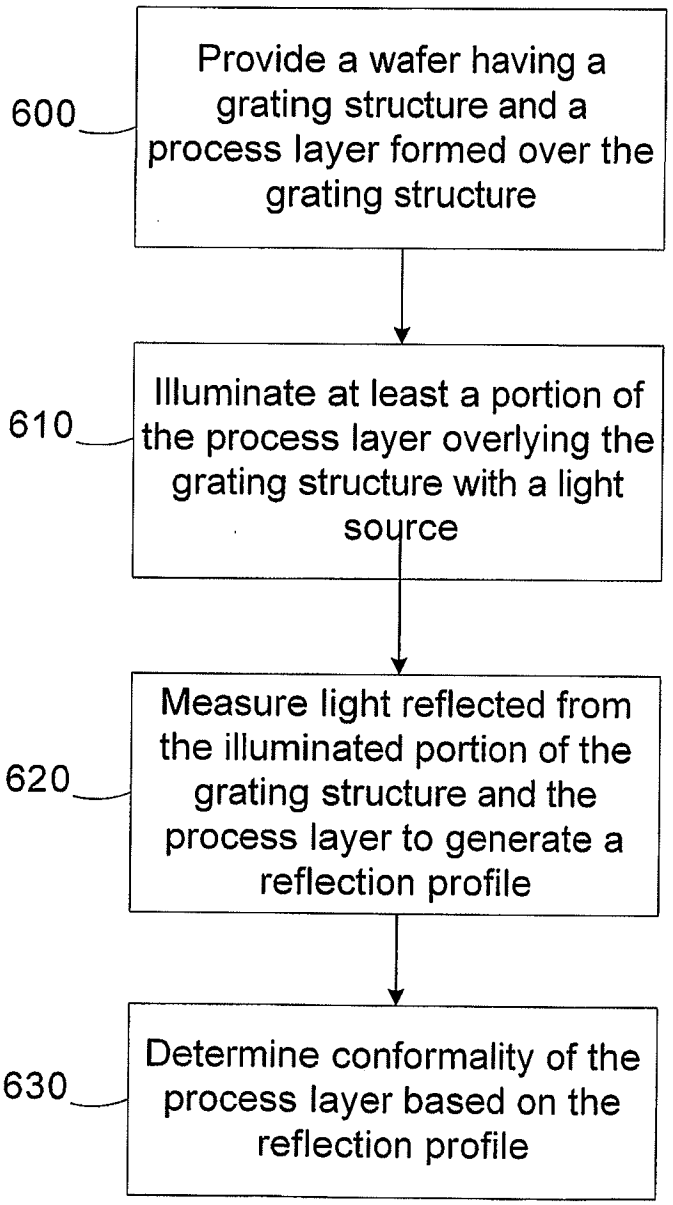

600
Provide a wafer having a grating structure and a process layer formed over the grating structure
610
Illuminate at least a portion of the process layer overlying the grating structure with a light source
620
Measure light reflected from the illuminated portion of the grating structure and the process layer to generate a reflection profile
630
Determine conformality of the process layer based on the reflection profile

Figure 6